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March 22 , 2006

To: Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, NY 12603

Subject: | Serial No. 10/660,914. 09/12/03 |

Chao-Peng Chen et al.

METHOD TO PRINT PHOTORESIST LINES  
WITH NEGATIVE SIDEWALLS

#### SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty  
of disclosure under CFR 1.97-1.99 and 37 CFR 1.56.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States  
Postal Service as first class mail in an envelope addressed to: Commissioner for Patents,  
P.O. Box 1450, Alexandria, VA 22313-1450, on March 22 , 2006.

Stephen B. Ackerman, Reg. # 37761

Signature/Date SB Ackerman 3/22/06

Chemistry of a Chemically Amplified Negative Resist and Process Modification for Electron Beam Exposure, by Shigeki Yamamoto et al., Presented by Patrick Martens, Sumitomo Chemical America, discusses the chemistry of a chemically amplified negative resist and process modification for electron beam exposure.

Perpendicular Recording Head Technology, DASCOM Business Group, TDK Corporation, Japan, 07/23/02, p.5, discusses the ABS view of perpendicular head: Single Pole.

The paper "Bake Condition Effect on Hybrid Lithography Process for Negative Tone Chemically Amplified Resists," by L. Pain et al., Advances in Resist Technology and Processing XVII, Francis M. Houlihan, Editor, Proceedings of SPIE, Vol. 3999 (2000), 0277-786X/00, presents the process optimization study of negative tone Chemically Amplified Resists (CAR) under E-Beam exposure.

Sincerely,



Stephen B. Ackerman,  
Reg. No. 37761

Form PTO-1449

## INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Doctor Number (Optional)

HTIRC-02-013

Application Number

10/660,914

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Logiciel: Chao - Peng Chen et al.

Filing Date

09/12/03

Group 1st Unit

## U. S. PATENT DOCUMENTS

[illegible]

## FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

-	Chemistry of a Chemically Amplified Negative Resist and Process Modification for Electron Beam Exposure, by Shigeki Yamamoto et al., Presented by Patrick Martens, Sumitomo Chemical America.
-	Perpendicular Recording Head Technology, DASCOM Business Group, TDK Corp., Japan, 07/23/02, p.5.

**EXAMINER**

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

